

#211D
WB
8/16/01

Attorney Docket: 381AS/50311TR
PATENT



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: SHUICHI KANNO ET AL.

Serial No.: 09/005,006 Group Art Unit: 1754

Filed: JANUARY 9, 1998 Examiner: N. NGUYEN

Title: PROCESS FOR TREATING FLUORINE COMPOUND-
CONTAINING GAS

AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

The following amendments and remarks are respectfully
submitted in response to the Office Action mailed March 13,
2001.

IN THE CLAIMS:

Please amend Claim 24 as follows:

RECEIVED
AUG 16 2001
TC 1700 MAIL ROOM

24. (Amended) A process for treating a fluorine compound-
containing gas, which comprises contacting a gas stream
containing at least one of compounds consisting of carbon and
fluorine, compounds consisting of carbon, hydrogen and
fluorine, and compounds consisting of carbon, hydrogen, oxygen
and fluorine with a catalyst comprising aluminum and nickel as
metallic components in the form of single oxides or composite
oxides and showing a decomposition activity to carry out a
reaction with steam or a reaction gas comprising steam and
oxygen at a reaction temperature of 400° to 800°C, thereby
decomposing the fluorine compound to hydrogen fluoride and
carbon dioxide.

D1